



HJT 硅片管式吸杂前清洗设备-MW级

HJT Wafer Tube Cleaning Equipment -MW Level

特点描述

- 外循环式进风与主动排风相结合的烘干系统;
- 臭氧水洗采用常压大流量混合, 确保臭氧混合有效性;
- 冷/热水慢提拉工艺, 更宽的工艺窗口;
- 高效过滤与初效过滤相结合, 保证设备内更高的洁净度。

Features

- Drying system, combination of external circulating intake and active exhaust;
- Atmospheric mixed ozone washing, ensure mixing effectiveness;
- Cold/hot water slow lift process, wider process window;
- Combining efficient filtration with preliminary filtration, ensure higher cleanliness inside the device.

技术性能

设备产能>19200片/小时(每篮232片半片)(800MW@210半片、600MW@182半片);
碎片率<0.3‰;
反射率>40%,单片抛光均匀性<1%,片间抛光均匀性<1%;
台阶宽度大于15um;
设备Uptime≥97%;
设备臭氧水浓度>40ppm;
设备产品良率>99.9%。

Performance

Equipment capacity >19200Pcs/h(232pcs half cell per basket)
(800MW@210B、600MW@182B);
Breakage rate< 0.3‰;
Reflectivity> 40%, texture uniformity<1%,
Texture uniformity between cell<1%;
Step width greater than 15um;
Uptime: ≥97%;
Ozone concentration > 40 ppm;
Product yield >99.9%.

技术参数 Parameter

项目 Item	数值 Value
清洗流程 Cleaning process	O3-Clean→SDE→O3-Clean→DHF→DRY